Initial Wetting System - Introduction

The initial wetting of a luminium has a significant influence on the efficiency of the evaporation process.

The "Initia IW etting System" is characterized by an improvement of the initia Iwetting of a luminium.



Initial Wetting System – Status Quo

Break in difficulties of unused evaporators regarding we tability of a luminium

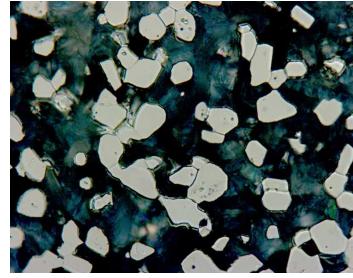
Reason for that difficulties:

- The unused evaporator consist of approx.65 Vol.% of Boron Nitride (BN) which is hard to wet by a luminium.
- Boron -Nitride (BN) is "alum inophob" because of the anisotropic crystal structure.



Structure of IMC-Evaporators

65 Vol% of Boron - Nitride (BN) which is hard to wet by a luminium.



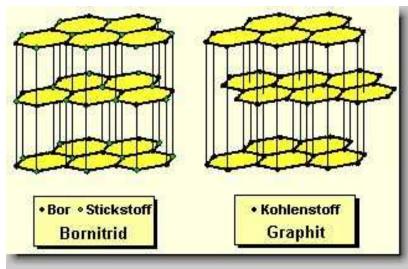
Etched Surface of an MC-Evaporator boat

Dark areas = BN

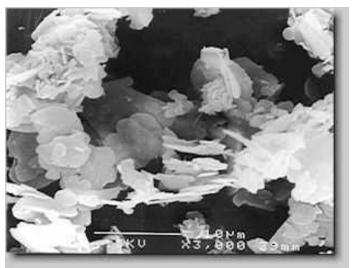
Light-cobured areas = TB_2



Crystal Structure of Boron-Nitride



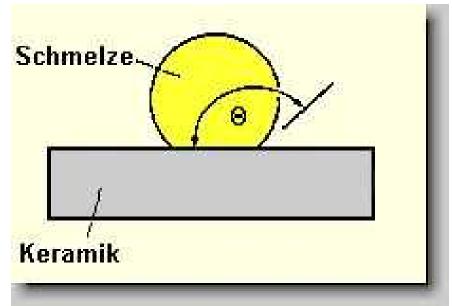
CrystalStructure of BN (Bornitrid) – schematically



Plates of BN; SEM - analysis (3000x; SE)



Wetablity in General



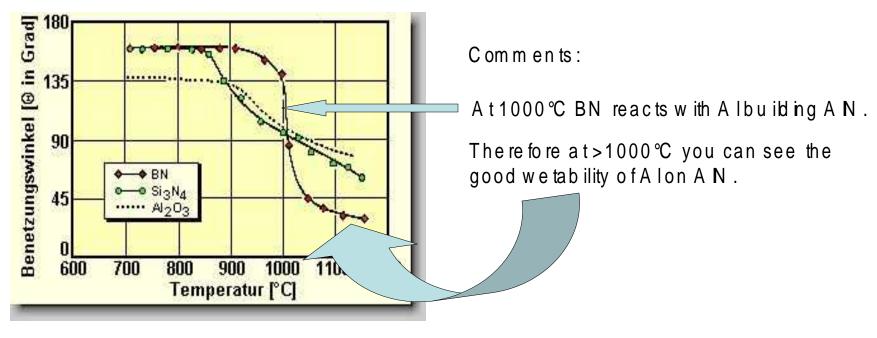
Definition of the "wetting angle of contact Θ " on ceramic substrates

Comment: Wetting angle of contact $\Theta > 90^\circ$: bad we tab ility

W etting angle of contact $\Theta < 90^{\circ}$: good we tab ility



Wetablity in General



W etability of a lum in ium on BN (A N), S $\frac{1}{5}N_4$, A $\frac{1}{2}O_3$ surfaces in dependence of the temperature



Vapour Pressure and Evaporation Temperature

Vaporpressure	Evaporation tem perature of Alin ℃
1 ,33 * 10 ⁻⁴ m ba r	920 °C
1,33 * 10 ⁻² m bar	1140 °C

Evaporation temperature of AI in dependence of the vapour pressure

Comments: You see that the liquid Al<u>evaporates before</u> building up the good we table AN at 1000 ℃. Therefore the aluminium can be only partial distributed on to the evaporator surface.



Some Questions

Why does evapora to r boats consist of BN?

BN provide:

- A very good the malshock resistance
- -The right specific resistivity (electrical insulator)
- A good mach nable material

What's the reason for good wetting of Alafter a certain time of continuously Al-feed?

BN get decomposed on the hotter, not we tted evaporator surface area during metallization

The remaining TB_2 of the evaporator boatmaterial is a wetting catalyzer.



Initial Wetting System - Theoretical Background

A) Components of the Initia IW etting System

"In it is IW etting System " = a combination of a lum in ium and a wetting agent

Compounds of the wetting agent: Tiand Si.



Initial Wetting System - Theoretical Background

B) First Heating Up of the Initia IW etting System

 $T = 700-1000 \,^{\circ}C$ The wetting agent reduces the "wetting angle of contact" of the AI This effect helps to <u>distribute the liquid A</u>I.

T = app rox . 1000 $^{\circ}\!C$ A I reacts with the BN of evaporator surface building A N . A lwets A N we II.

 $T>1000\,^\circ\!C$ The residual A levaporates. There remains a thin A N-byer which covers almost the whole cavity surface of the evaporator.



Initial Wetting System - Theoretical Background

C) Continuous AIW ire Feed

The thin AN-layer on the evaporator surface is wetted by Almuch better than BN

The wetting area is bigger than usual.

The wetting is more homogeneous than usual.

By proper running conditions the good wetting can be maintained from the beginning to the end of the evaporator boat life.



Initial Wetting System – Possible Concern

A) Toxicity

The wetting agents consist of a compound of Titanium and Silicon.

=> Both elements are not critical with regard to food contact.



Initial Wetting System – Possible Concern

B)Quantities – A Cakulation Example

In a 99,8% A I-w ire (99,8%) can be found Titanium and Silicon as impurities as follows: Ti = approx. 0,02% Si = approx. 0,15%

S in tec uses only a very small quantity of that T itan ium -S ilicon -compound: $1 - 2 \text{ mg/cm}^2 = approx \cdot 20 - 60 \text{ mg/boat}$

=> 15-40 g A I-w ire (99,8%) does contain the same quantity of Sias the WS



Initial Wetting System – Possible Concern

C) Analysis

No Titanium and Silicon increase in the metallized film could be detected.

The Tiand Sipossbly remains <u>on to the shutter</u> before starting metallization



Initial Wetting System – Visualization

- a) Video 1: In it is I wetting without "In it is IW etting system"
- b) Video 2: In it is I wetting with "In it is IW etting System"

